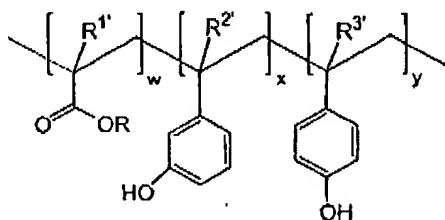


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This listing of claims will replace all prior versions of claims in the application.

Claims 1-34. (cancelled)

Claim 35. (new) A positive-acting photoresist composition comprising a photoacid generator compound and a polymer represented by the following formula:



wherein R is tert-butyl;

R<sup>1'</sup>, R<sup>2'</sup> and R<sup>3'</sup> are each independently hydrogen or methyl;

w, x, and y are each greater than 0 and are mole percents of the respective units of the polymer and the sum of x, y and z is 100 percent, and w is 5 to 25 mole percent.

Claim 36. (new) The photoresist composition of claim 35 wherein x is greater than y.

Claim 37. (new) The photoresist composition of claim 35 wherein x is 50 to 85 mole percent and y is 8 to 35 mole percent.

Claim 38. (new) The photoresist composition of claim 35 wherein R<sup>1</sup> and R<sup>2</sup> are each hydrogen.

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Claim 39. (new) The photoresist composition of claim 35 wherein w is 8 to 20 mole percent; x is 60 to 75 mole percent; and y is 10 to 25 mole percent.

Claim 40. (new) The photoresist composition of claim 35 wherein w is 8 to 20 mole percent; x is 60 to 70 mole percent; and y is 10 to 20 mole percent.

Claim 41. (new) The photoresist composition of claim 35 wherein the polymer has a molecular weight distribution of 3 or less.

Claim 42. (new) The photoresist composition of claim 35 wherein the polymer has a molecular weight distribution of 2 or less.

Claim 43. (new) The photoresist composition of claim 35 wherein the polymer has a weight average molecular weight of 5,000 to 25,000.

Claim 44. (new) The photoresist composition of claim 35 wherein the photoresist composition consists essentially of the polymer and photoacid generator.